

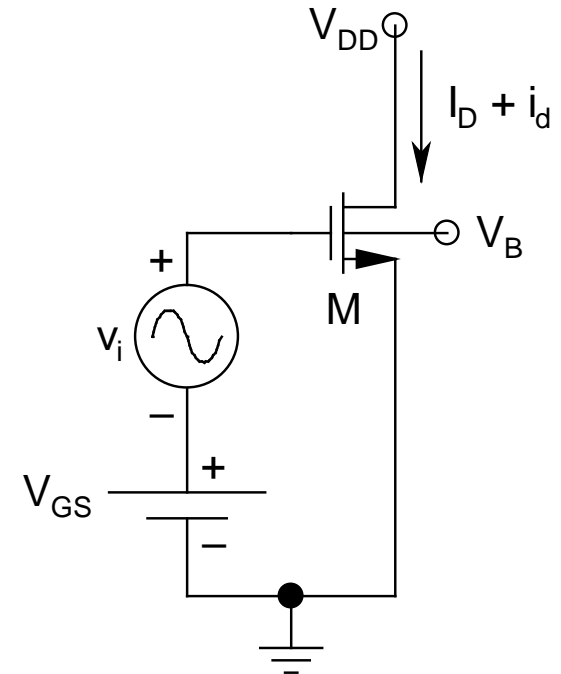
Small-Signal Model

- The *electrical equivalent* of the MOSFET at the *DC bias point*
- *Must be biased in saturation*
 - *Resembles a constant current source*
- *DC analysis must precede*, since *need the information regarding the Q-point* (I_D , V_{DS})
- *This model for NMOS and PMOS is the same (incremental model)*

Validity of the Small-Signal Model

- The *instantaneous current* (assuming $\lambda V_{DS} < 0.1$):

$$\begin{aligned} I_d &= \frac{k_N}{2} (V_{GT} + v_i)^2 \\ &= I_D + \frac{k_N}{2} [2V_{GT}v_i + v_i^2] \\ \Rightarrow i_d &= k_N V_{GT} v_i \left[1 + \frac{v_i}{2V_{GT}} \right] \end{aligned}$$



- Thus, for *linear relationship* between i_d and v_i , *v_i must be $\ll 2V_{GT}$*
- Note that $V_{GT}(\text{minimum}) = 3V_T$
- Hence, *v_i should be less than $1/10^{\text{th}}$ of $6V_T$*
(requirement less rigorous than BJT)
- Recall in *BJT*, for *linear relationship* between i_c and v_i , *v_i has to be less than $1/10^{\text{th}}$ of V_T*
 - *Six times less than that for MOSFET*
 - *MOSFETs are inherently more linear device than BJT (compare quadratic with exponential)*

Small-Signal Model Parameters

- *Transconductance* (g_m):

$$g_m \triangleq \left. \frac{\partial I_D}{\partial V_{GS}} \right|_{V_{DS} \text{ and } V_{SB} \text{ constant}}$$
$$= k_N V_{GT} (1 + \lambda V_{DS}) = \sqrt{2k_N I_D (1 + \lambda V_{DS})}$$

➤ *If $\lambda V_{DS} < 0.1$:*

$$g_m \simeq k_N V_{GT} \simeq \sqrt{2k_N I_D}$$

- An important *Figure of Merit* is *transconductance to current ratio*
 - For *MOSFETs*: $g_m/I_D = 2/V_{GT}$
 - For *BJTs*: $g_m/I_C = 1/V_T$
 - Thus, *BJTs produce more g_m per unit current*
- As we will see later, a *high value of g_m is highly desirable*, since it *dictates the gain*
- *g_m/I_D can be changed by changing the bias current and/or aspect ratio*
- *g_m/I_C is a function only of temperature*

- **Body Transconductance** (g_{mb}):

$$g_{mb} \triangleq \left. \frac{\partial I_D}{\partial V_{BS}} \right|_{V_{GS} \text{ and } V_{DS} \text{ constant}} = \chi g_m$$

$$\chi = \frac{\gamma}{2\sqrt{2\phi_F + V_{SB}}} = \textit{Body factor} \quad (\sim 0.1-0.3)$$

- *Note: As $V_{SB} \uparrow$, $V_{TN} \uparrow \Rightarrow I_D \downarrow$*
- *$\partial I_D / \partial V_{SB}$ would have yielded negative g_{mb}*
- *If both B and S are tied to fixed DC potentials (including ground), g_{mb} won't matter!*

- **Output Conductance** (g_0)/

Output Resistance (r_0):

$$g_0 = r_0^{-1} \triangleq \left. \frac{\partial I_D}{\partial V_{DS}} \right|_{V_{GS} \text{ and } V_{SB} \text{ constant}} = \frac{\lambda I_D}{1 + \lambda V_{DS}}$$

➤ **If $\lambda V_{DS} < 0.1$:**

$$g_0 = 1/r_0 \approx \lambda I_D$$

➤ **λ has a very wide range ~ 0.01 - 0.5 V^{-1}**

➤ **When $\lambda \rightarrow 0$, $g_0 \rightarrow 0$, and $r_0 \rightarrow \infty$**

- **Device starts to behave like an ideal constant current source**

- *Gate-Source and Gate-Drain Capacitance*

(C_{gs} and C_{gd}):

- Each has *two components*: *intrinsic* (i) and *technological* (t)

- *Total intrinsic gate-body capacitance*:

$$C_{gbi} = C'_{ox} WL$$

- Using *Meyer's model*, *intrinsic component*:

- In *linear region*: $C_{gsi} = C_{gdi} = C_{gbi}/2$

- In *saturation region*: $C_{gsi} = (2/3)C_{gbi}$, $C_{gdi} = 0$

- *Technology component arises due to gate-source and gate-drain overlap* (L_D)

➤ *Technology components:*

$$C_{gst} = C_{gdt} = C'_{gs0} W = C'_{gd0} W$$

Gate-Source/Drain Overlap Capacitance

per unit width: $C'_{gs0} = C'_{gd0} = C'_{ox} L_D$

➤ Thus, *total capacitance in saturation:*

$$C_{gs} = (2/3) C'_{ox} WL + C'_{gs0} W$$

$$C_{gd} = C'_{gd0} W$$

➤ $C_{gs} \gg C_{gd}$

- ***Source-Body and Drain-Body Capacitance***

(C_{sb} and C_{db}):

➤ ***Both reverse-biased n^+p junctions***

$$C_{sb} = \frac{C_{sb0}}{(1 + V_{SB}/V_0)^m} \quad \text{and} \quad C_{db} = \frac{C_{db0}}{(1 + V_{DB}/V_0)^m}$$

$$C_{sb0} = C_{sb} \big|_{V_{SB}=0} \quad \text{and} \quad C_{db0} = C_{db} \big|_{V_{DB}=0}$$

$$V_{SB} \text{ and } V_{DB} \geq 0$$

- ***Drain/Source Series Resistance*** (R_S and R_D):

➤ ***Due to neutral n^+ source/drain regions***